

10-24-'06 10:50 FROM-LGS PatentUSA

+9549251101

T-286 P02/13 U-932

Appl. No. 10/717,413  
Amdt. dated 10/24/06  
Reply to Office action of 7/24/06

CLAIM AMENDMENTS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1 - 10 (canceled).

Claim 11 (original). A method for adjusting a substrate in an exposure appliance used for transferring a structure to the substrate, the appliance including a moving chuck for aligning the substrate, a radiation source, and at least one focusing device, the method which comprises:

for at least one first position on the chuck, obtaining a measured discrepancy by measuring any discrepancy between a surface of the chuck and an idealized plane;

providing the substrate, which is covered with a photosensitive layer, on the chuck such that the surface of the chuck faces the substrate;

selecting a first detail from a plurality of details provided for measuring an ideal focus distance in the photosensitive layer, the first detail representing a first exposure area on the substrate, the selecting step including defining a

Appl. No. 10/717,413  
Amdt. dated 10/24/06  
Reply to Office action of 7/24/06

projected first position by projecting the first position on the chuck into the photosensitive layer and selecting the first detail such that the projected first position is located within or near the first detail;

setting a predetermined limit value for a permissible discrepancy;

comparing the measured discrepancy with the predetermined limit value;

as a function of the comparing step, excluding a detail from the plurality of details provided for measuring the ideal focus distance in the photosensitive layer;

obtaining a measured ideal focus distance by measuring a focus distance being ideal for exposure in at least one further detail from the plurality of details; and

moving the chuck to adjust the substrate to the measured ideal focus distance for illuminating the first exposure area.

Claim 12 (original). A method for adjusting a substrate in an exposure appliance used for transferring a structure to

Appl. No. 10/717,413  
Amdt. dated 10/24/06  
Reply to Office action of 7/24/06

the substrate, the appliance including a moving chuck for aligning the substrate, a radiation source, and at least one focusing device, the method which comprises:

for at least one first position on the chuck, obtaining a measured discrepancy by measuring any discrepancy between a surface of the chuck and an idealized plane;

providing the substrate, which is covered with a photosensitive layer, on the chuck such that the surface of the chuck faces the substrate;

selecting a first detail including at least one first adjustment mark from a plurality of details in the photosensitive layer, the first detail representing a first exposure area on the substrate, the selecting step including defining a projected first position by projecting the first position on the chuck into the photosensitive layer and selecting the first detail such that the projected first position is located within or near the first detail;

setting a predetermined limit value for a permissible discrepancy;

10-24-'06 10:50 FROM-LGS PatentUSA

+9549251101

T-286 P05/13 U-932

Appl. No. 10/717,413  
Amdt. dated 10/24/06  
Reply to Office action of 7/24/06

comparing the measured discrepancy with the predetermined limit value;

as a function of the comparing step, not considering the adjustment mark in the first detail; and

based on at least one further adjustment mark, moving the chuck to adjust the substrate in a direction at right angles to a direction of a focus distance for illuminating the first exposure area.